	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO.		SERIAL NO.			
			251475US3DIV		New Application			
			APPLICANT					
LIST OF REFERENCES CITED BY APPLICANT		Kousaku MATSUNO, et al.						
			FILING DATE		GROUP			
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	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE		
AA	6,080,531	06/27/00	Carter et al.	†				
AB	5,971,368	10/26/99	Nelson et al.					
AC	5,983,909	11-1999	Yeol et al.					
AD	6,920,777	09-2001	lmaoka et al.					
AE	6,325,359	12-2001	Haga et al.					
AF	5,503,708	04-1996	Koizumi et al.					
AG	6,086,057	07-2000	Mitsumori et al.					
АН	6,039,815	03-2000	Yeol et al.					
Al	6,035,871	03-2000	Eui-Yeol, Oh	 				
AJ	4,812,201	03-1989	Sakai et al.					
AK	5,783,790	07-1998	Mitsumori et al.					
AL	6,217,665	04-2001	Suzuki			· · · · · · · · · · · · · · · · · · ·		
АМ	5.739,575	04-1998	Numano et al.					
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	NUMBER	DATE	COUNTRY			TRANSLATION YES NO		
AO	8-78372	03-1996	Japan (w/ abstract)	***	·	xx		
AP	63-271938	11-1988	Japan (w/ abstract)			xx		
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S. Nelson: Using an ozone water last cleaning process to research the effects of process parameters on water contamination; SPWCC, pp. 230-242, March 4-7, 1996								
AX	M. Hiroshi et al.: Dissolved-Gas Controlled Ultrapure Water Production System for Wet Cleaning Processes; The seventh International symposium on semiconductor manufacturing, proceedings of ISSM '98, Tokyo, pp. 428-431 (1998)							
AY	M. Hiroshi et al.: Advanced UCT Cleaning Process Based on Specific Gases Dissolved Ultrapure Water; The eighth International symposium on semiconductor manufacturing, proceedings of ISSM '99 Tokyo, pp. 453-456 (1999)							
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	AA AB AC AD AE AF AG AH AN AN AN AV AX AY AZ	DOCUMENT NUMBER AA 6,080,531 AB 5,971,368 AC 5,983,909 AD 6,920,777 AE 6,325,359 AF 5,503,708 AG 6,086,057 AH 6,039,815 AI 6,035,871 AJ 4,812,201 AK 5,783,790 AL 6,217,665 AM 5.739,575 AN DOCUMENT NUMBER AO 8-78372 AP 63-271938 AQ AR AS AT AU AV OTHER RE AW S. Nelson: Using an occontamination; SPWCC AX M. Hiroshi et al.: Dissocuted and the contamination of t	DOCUMENT NUMBER DATE	REFERENCES CITED BY APPLICANT REFERENCES CITED BY APPLICANT REFERENCES CITED BY APPLICANT ROUSAKU MATSUNO, et al. FILING DATE Herewith U.S. PATENT DOCUMENTS DOCUMENT NUMBER AA 6,080,531 D6/27/00 Carter et al. AB 5,971,368 10/26/99 Nelson et al. AC 5,983,909 11-1999 Yeol et al. AD 6,920,777 D9-2001 Imaoka et al. AE 6,325,359 12-2001 AE 6,325,359 12-2001 AF 5,503,708 AF 1996 Koizumi et al. AG 6,086,057 O7-2000 Mitsumori et al. AI 6,039,815 D3-2000 Eu-Yeol, Oh AJ 4,812,201 D3-1989 Sakai et al. AK 5,783,790 O7-1998 Mitsumori et al. AL 6,217,665 D4-2001 Suzuki AM 5,739,575 D4-1998 Numano et al. AN FOREIGN PATENT DOCUMENTS DOCUMENT NUMBER DATE COUNTRY AO 8-78372 D3-1996 Japan (w/ abstract) AQ AV OTHER REFERENCES (Including Author, Title, Date, Pertinent Authors and Companies of the Country of the	REFERENCES CITED BY APPLICANT REFERENCES CITED BY APPLICANT ROUGHENT DOCUMENT NUMBER DATE NAME CLASS AA 6.080.531 D6/27/00 Carter et al. AC 5.983.909 11.1999 Yeol et al. AD 6.920,777 D9-2001 Imaoka et al. AE 6.325.359 12-2001 Haga et al. AF 5.503,708 A4-1996 Koizumi et al. AG 6.086.057 O7-2000 Mitsumori et al. AI 6.039.815 D3-2000 Pelo et al. AI 6.035,871 D3-2000 Pelo et al. AI 6.037,875 AI 1998 Mitsumori et al. AI 6.217,665 O4-2001 Suzuki AM 5.739,575 D4-1998 Numano et al. FOREIGN PATENT DOCUMENTS DOCUMENT NUMBER DATE COUNTRY AD 8-78372 D3-1996 Japan (w/ abstract) AP 63-271938 11-1988 Japan (w/ abstract) AV OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, et international symposium on semiconductor manufacturing, proceedings of ISSM '98, Tok AY M. Hiroshi et al.: Dissolved-Gas Controlled Ultrapure Water Production System for Well of International symposium on semiconductor manufacturing, proceedings of ISSM '99, Tok AY M. Hiroshi et al.: Advanced UCT Cleaning Process Based on Specific Gases Dissolved Uniternational symposium on semiconductor manufacturing, proceedings of ISSM '99, Tok AY M. Hiroshi et al.: Development of ozonated ultra-pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, Date Date Constability of the pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, Date Constability of the pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, Date Constability of the pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, Date Constability of the pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16, Date Constability of the pure water supplying system using direct-dissolving method, SPWCC, pp. 51-60, March 13-16	REFERENCES CITED BY APPLICANT REFERENCES CITED BY APPLICANT COUMENT NUMBER A6,080,531 DOCUMENT NUMBER A7,080,591 A8,080,531 DOCUMENT NUMBER A8,080,531 DOCUMENT NUMBER A9,080,531 DOCUMENT NUMBER A1,080,531 DOCUMENT NUMBER A2,080,531 DOCUMENT NUMBER A3,080,531 DOCUMENT NUMBER A6,080,531 DOCUMENT NUMBER A7,080,390 DOCUMENT NUMBER A8,080,539 DOCUMENT NUMBER A1,092,0777 DOCUMENT NUMBER A8,030,815 DOCUMENT NUMBER A9,030,815 DOCUMENT NUMBER DATE COUNTRY POREIGN PATENT DOCUMENTS POREIGN PATENT DOCUMENTS COUNTRY YES A0,032,3708 DOCUMENT NUMBER DATE COUNTRY YES A0,032,3709 DOCUMENT NUMBER DATE COUNTRY YES A0,032,3709 DOCUMENT NUMBER DATE COUNTRY YES A0,3790,3790 AN,4790,3790 AN,4790,4790,4790 AN,4790,4790,4790 AN,4790,4790,4790 AN,4790,4790 AN,4790,4790 AN,4790,4790 AN,47900,4790 AN		

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE	ATTY DOCKET NO.	SERIAL NO.					
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MK	AAB	Werner Kern. Handbook of Semiconductor Cleaning Technology, 1993, Noyes Publications, Page 120.							
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